

## PLASMA PROCESSING APPARATUS AND METHOD FOR CONTROLLING POWER STORAGE AMOUNT

### Abstract

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A disclosed plasma processing device comprises a plasma processing chamber, a substrate support part, a ground frame, a power storage unit, a rectification and smoothing unit, a power supply output connector, and a power reception coil. The ground frame is grounded and, together with the plasma processing chamber, surrounds the substrate support part. The power storage unit and the rectification and smoothing unit are disposed in a space surrounded by the ground frame. The rectification and smoothing unit includes a power supply input connector and a rectification circuit. The power supply input connector is provided so as to be accessible from the outside of the ground frame. The rectification circuit includes a diode bridge, and is connected between the power supply input connector and the power storage unit. The power supply output connector is connected to the power reception coil, and is attachable to and detachable from the power supply input connector.

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Fig. 29